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REMARKS

Reconsideration of this application is respectfully requested. The present invention relates to chemical-mechanical polishing compositions comprising amine-containing polymers. Claims 1-17 currently are pending.

Claims 12-17 are allowed. The indication that claims 5 and 6 would be allowable if written in independent form is noted with appreciation. To that end, claims 5 and 6 have been rewritten in independent form.

Claim 1 has been amended to more particularly point out and distinctly claim the subject matter which Applicants regard as their invention. In particular, the claim has been amended to delete the term "about" previously used in connection with the sequential atoms separating the nitrogen atoms of the amino functional groups in subsection (c). No new matter has been added by way of these amendments.

Claims 1-3 and 7-8 stand rejected under 35 U.S.C. § 102(b) as anticipated by Japanese Patent Application Publication No. 11-302633 to Miyashita et al. ("the '633 publication"). This rejection is respectfully traversed. The '633 publication does not disclose a polishing system including an amine-containing polymer with 5 or more sequential atoms separating the nitrogen atoms (of the amino groups). Applicants respectfully disagree with the assertion that the claim language "...about 5 or more..." is met by the '633 publication (28 October 04 Office Action, p. 4, ¶9). Claim 1 has been amended to remove the word "about" and avoid confusion regarding the scope of this claim limitation. Claims 2-3 and 7-8 depend from claim 1 and are allowable for the same reasons. Withdrawal of this rejection is requested.

The rejection of claims 1-4 and 7-10 under 35 U.S.C. § 102(a) as anticipated by WIPO Publication No. WO 01/12740 A1 to Wang et al. ("the Wang '740 publication") is respectfully traversed. The '740 publication also does not disclose a polishing system including an amine-containing polymer with 5 or more sequential atoms separating the nitrogen atoms (of the amino groups). Applicants likewise respectfully disagree with the assertion that the claim language "...about 5 or more..." is met by the '740 publication. To the extent the '740 publication discloses the addition of additives that can be labeled "polymers," none of these additives have more than two sequential atoms separating the nitrogen atoms of their amino functional groups. Claims 2-4 and 7-10 are dependent from claim 1 and not anticipated for the same reasons. Withdrawal of the rejection is requested.

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The rejection of claims 9-11 under 35 U.S.C. § 103(a) as being unpatentable over the Miyashita '633 publication in view of U.S. Patent 6,478,834 issued to Tsuchiya et al. ("the '834 patent") is traversed for the same reasons. The Tsuchiya '834 patent provides examples of higher-mono-primary amines, none of which are amine-containing polymers or amine-containing polymer with about 5 or more sequential atoms separating the nitrogen atoms of the amino functional groups. Therefore, the '834 patent does not address the disclosure required from the primary reference (the '633 publication). Accordingly, claims 9-11 are patentable over and not obvious in view of the cited references.

The present amendments to the claims and the accompanying discussion are believed to dispose of all issues in this case and to place this application in condition for allowance. Entry of the amendments, which is of course discretionary, and passing of this application to issue is respectfully requested. If, in the opinion of the Examiner, a telephone conference would expedite the prosecution of the subject application, the Examiner is invited to call the undersigned attorney.

Respectfully submitted,

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